

FORM PTO-1449/A and B (Modified)			APPLICATION NO.: 10/763,819	ATTY. DOCKET NO.: H0498.70130US01
INFORMATION DISCLOSURE STATEMENT BY APPLICANT			FILING DATE: January 23, 2004	CONFIRMATION NO.: Not yet assigned
			APPLICANT: Tao Deng et al.	
Sheet	1	of	2	GROUP ART UNIT: Not yet assigned 1756 EXAMINER: Not yet assigned DUDA

U.S. PATENT DOCUMENTS

Examiner's Initials#	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication or of issue of Cited Document MM-DD-YYY
		Number	Kind Code		
ICM	*A1	3,574,933	B1	Cassingham	04/13/71
	*A2	3,615,483	B1	Jonker et al.	10/26/71
	*A3	3,622,322	B1	Brill	11/23/71
	*A4	3,655,383	B1	Shepard et al.	04/11/72
	*A5	3,671,754	B1	Mundkur	06/20/72
	*A6	3,677,644	B1	Harris	07/18/72
	*A7	3,772,078	B1	Polichette et al.	11/13/73
	*A8	3,779,761	B1	Dustin	12/18/73
	*A9	3,880,726		Sakaki	04-1975
	*A10	3,900,614	B1	Lando	08/19/75
	*A11	4,059,445	B1	Sato	11/22/77
	*A12	4,104,111	B1	Mack	08/01/78
	*A13	4,133,908	B1	Madsen	01/09/79
	*A14	4,260,677	B1	Winslow et al.	04/07/81
	*A15	4,311,381	B1	Nettesheim et al.	01/19/82
	*A16	4,390,612	B1	Rutledge	06/28/83
	*A17	4,511,641	B1	Busman et al.	04/16/85
	*A18	4,560,643	B1	Finter et al.	12/24/85
	*A19	4,603,100	B1	Boston	07/29/86
	*A20	4,666,818	B1	Lake et al.	05/19/87
	*A21	4,871,671	B1	Errede et al.	10/03/89
	*A22	4,873,170	B1	Nishinoiri et al.	10/10/89
	*A23	4,910,118	B1	Adair et al.	03/20/90
	*A24	5,208,126	B1	Tachikawa et al.	05/04/93
	*A25	5,352,651	B1	Debe et al.	10/04/94
	*A26	5,443,713	B1	Hindman	08/22/95
	*A27	5,468,603	B1	Kub	11/21/95
	*A28	5,512,162	B1	Sachs et al.	04/30/96
	*A29	5,576,074	B1	Weigel et al.	11/19/96
	*A30	5,576,135	B1	Nishikawa	11/19/96
	*A31	5,589,307	B1	Takeuchi	12/31/96
	*A32	5,595,637	B1	Tench et al.	01/21/97
	*A33	5,681,441	B1	Svendsen et al.	10/28/97
	*A34	5,919,402	B1	Murphy et al.	07/06/99
	*A35	6,020,862	B1	Newton et al.	02/01/00
PLD	A36	6,706,165	B2	Deng et al.	03-16-2004



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**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

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of

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APPLICATION NO.: 09/755,645
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ATTY. DOCKET NO.: H0498/7130

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APPLICANT: Tao Deng et al.

GROUP ART UNIT: Not Yet Assigned
1756

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DUDA

FOREIGN PATENT DOCUMENTS

Examiner's Initials#	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document (not necessary)	Date of Publication of Cited Document MM-DD-YYYY	Translation (Y/N)
		Office/ Country	Number	Kind Code			
(KTD)	*A3	DD	153 950	A	Gesemann et al.	10.02.82	Y (Abstract)
(KTD)	*A3	EP	0 057 268	A2	International Business Machines Corp.	11.08.82	
(KTD)	*A3	GB	2 150 596	A	P A Consulting Services Limited	03.07.85	
(KTD)	*A4	JP	04099342	A	Matshushita Electric Ind. Co. Ltd.	31.03.92	Y (Abstract)
(KTD)	*A4	JP	07221418	A	Furukawa Electric Co. Ltd.	18.08.95	Y (Abstract)

OTHER ART — NON PATENT LITERATURE DOCUMENTS

Examiner's Initials#	Cite No	Include name of the author (in CAPITAL LETTERS) title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, relevant page(s), volume-issue number(s), publisher, city and/or country where published.	Translation (Y/N)
(KTD)	*A42	International Search Report Application No. PCT/US 01/00366 dated 03.09.01	
	*A43	KELLER, K. "Science and Technology of Photography," VCH: Weinheim, German, 1993	
	*A44	BJELKHAGEN, H.I., "Silver-Halide Recording Materials for Holography and Their Processing," Springer-Verlag: New York, 1995	
	*A45	ZHANG, Y. et al., "Electroless Copper Deposition in the Photographic Gelatin Layer," <i>Journal of the Electrochemical Society</i> , 146 (4), 1270-1272, 1999	
	*A46	LIDE, D.R., "CRC Handbook of Chemistry and Physics," CRC Press, New York, 1999	
	*A47	XIA, Y. et al. "Soft Lithography," <i>Agnew. Chem. Int. Ed.</i> , 1998, 37, p. 550-575	
	*A48	XU, B. et al. "Making Negative Poisson's Ratio Microstructures by Soft Lithography," <i>Adv. Materials</i> in Press 1999	
	*A49	KIRK-OTHMER Encyclopedia of Chemical Technology, 4 th Edition, 1999, p. 1541	
(KTD)	A50	DENG, T., et al., "Fabrication of Metallic Microstructure Using Exposed, Developed Silver Halide-Based Photographic Film," <i>Anal Chem.</i> 2000, 72, 645-651	

EXAMINER

K. Duda

DATE CONSIDERED

6-8-06

#EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

*a copy of this reference is not provided as it was previously cited or submitted to the office in a prior application, Serial No. 09/755,645, filed January 5, 2001, and relied upon for an earlier filing date under 35 U.S.C. 120 (continuation, continuation-in-part, and divisional applications).